

Ifw

Docket Number: 081468-0307331  
Client Reference: P-1774.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of

VAN SANTEN et al.

Group Art Unit: 2851

Application No.: 10/743,271

Examiner: Unassigned

Filed: December 23, 2003

Confirmation No.: 4441

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

January 7, 2005

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

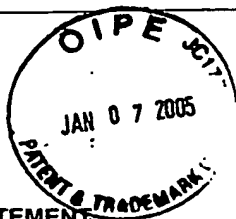
Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

| Examiner's Initials | First Inventor   | Application No. | Filing Date | Enclosed   |
|---------------------|--|-----------------|-------------|--|
|                     | DUINEVELD et al.<br>(081468-0308101)                                       | 10/773,461      | 02/09/2004  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | FLAGELLO et al.<br>(081468-0302644)  | 10/698,012      | 10/31/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | DIERICHS<br>(081468-0308270)   | 10/775,826      | 02/11/2004  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | SUWA et al.<br>(Reissue Application of<br>U.S. Patent No. 6,191,429<br>B1) | 10/367,910      | 02/19/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input type="checkbox"/> Other: stamped receipt card            |

\*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.



|                   |        |               |
|-------------------|--------|---------------|
| Atty.<br>Dkt. No. | M#     | Client Ref.   |
|                   | 307331 | P-1774.000-US |

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

|                                |                      |
|--------------------------------|----------------------|
| Applicant: VAN SANTEN et al.   |                      |
| Appln. No. 10/743,271          |                      |
| Filing Date: December 23, 2003 |                      |
| Examiner: Unknown              | Group Art Unit: 2851 |

Date: January 7, 2005

Page 1 of 4

**U.S. PATENT DOCUMENTS**

| Examiner's<br>Initials | Document<br>Number | Date<br>MM/YYYY | Name<br>(Family Name of First Inventor) | Class | Sub<br>Class | Filing Date<br>(if appropriate) |
|------------------------|--------------------|-----------------|---|-------|--------------|---------------------------------|
| HN                     | AR 3,573,975       | 04/1971         | DHAKA et al.                            | 117   | 212          |                                 |
|                        | BR 3,648,587       | 03/1972         | STEVENS                                 | 95    | 44           |                                 |
|                        | CR 4,346,164       | 08/1982         | TABARELLI et al.                        | 430   | 311          |                                 |
|                        | DR 4,390,273       | 06/1983         | LOEBACH et al.                          | 355   | 125          |                                 |
|                        | ER 4,396,705       | 08/1983         | AKEYAMA et al.                          | 430   | 326          |                                 |
|                        | FR 4,480,910       | 11/1984         | TAKANASHI et al.                        | 355   | 30           |                                 |
|                        | GR 4,509,852       | 04/1985         | TABARELLI et al.                        | 355   | 30           |                                 |
|                        | HR 5,040,020       | 08/1991         | RAUSCHENBACH et al.                     | 355   | 53           |                                 |
|                        | IR 5,121,256       | 06/1992         | CORLE et al.                            | 359   | 664          |                                 |
|                        | JR 5,610,683       | 03/1997         | TAKAHASHI                               | 355   | 53           |                                 |
|                        | KR 5,715,039       | 02/1998         | FUKUDA et al.                           | 355   | 53           |                                 |
|                        | LR 5,825,043       | 10/1998         | SUWA                                    | 250   | 548          |                                 |
|                        | MR 5,900,354       | 05/1999         | BATCHELDER                              | 430   | 395          |                                 |
| HN                     | NR 6,191,429       | 02/2001         | SUWA                                    | 250   | 548          |                                 |

**FOREIGN PATENT DOCUMENTS**

|    | Document<br>Number | Date<br>MM/YYYY | Country | Inventor Name    | English Abstract |    | Translation<br>Readily<br>Available |    |
|----|--------------------|-----------------|---------|------------------|------------------|----|-------------------------------------|----|
|    |                    |                 |         |                  | Enclosed         | No | Enclosed                            | No |
| HN | OR WO 99/49504     | 09/1999         | PCT     | FUKAMI et al.    | X                |    | X                                   |    |
|    | PR EP 0023231      | 02/1981         | EUROPE  | TABARELLI et al. | X                |    |                                     |    |
|    | QR EP 0418427      | 03/1991         | EUROPE  | MIYAKE           | X                |    | X                                   |    |
|    | RR EP 1039511      | 09/2000         | EUROPE  | MURAKAMI et al.  | X                |    | X                                   |    |
|    | SR DD 224448       | 07/1985         | GERMANY | HESSE et al.     |                  | X  |                                     |    |
|    | TR DD 242880       | 02/1987         | GERMANY | KUCH             |                  | X  |                                     |    |
|    | UR FR 2474708      | 07/1981         | FRANCE  | LETELLIER        |                  | X  |                                     |    |
|    | VR JP 62-065326    | 03/1987         | JAPAN   | MORIUCHI         | X                |    |                                     |    |
|    | WR JP 62-121417    | 06/1987         | JAPAN   | NAKAZAWA         | X                |    |                                     |    |
|    | XR JP 63-157419    | 06/1988         | JAPAN   | NAKASUJI         | X                |    |                                     |    |
|    | YR JP 04-305915    | 10/1992         | JAPAN   | OZEKI et al.     | X                |    |                                     |    |
|    | ZR JP 04-305917    | 10/1992         | JAPAN   | OZEKI et al.     | X                |    |                                     |    |
| HN | AAR JP 06-124873   | 05/1994         | JAPAN   | TAKAHASHI        | X                |    | X                                   |    |

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

|    |     |   |  |  |  |
|----|-----|---|--|--|--|
| HN | BBR | M. SWITKES et al., "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001                              |  |  |  |
|    | CCR | M. SWITKES et al., "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356 |  |  |  |
| HN | DDR | M. SWITKES et al., "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002                                |  |  |  |

Examiner H. Nguyen Date Considered: 6/13/05

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

|  |  |      |   |                                |    |                      |  |
|--|--|------|---|--------------------------------|----|----------------------|--|
| FORM PTO-1449 (modified)<br>To: U.S. Department of Commerce<br>(PW FORM PAT-1449)<br>Patent and Trademark Office |  |      |   | Atty.<br>Dkt. No.              | M# | Client Ref.          |  |
|  |  |      |   | 307331                         |    | P-1774.000-US        |  |
| <b>INFORMATION DISCLOSURE STATEMENT<br/>BY APPLICANT</b>   |  |      |   | Applicant: VAN SANTEN et al.   |    |                      |  |
|  |  |      |   | Appln. No. 10/743,271          |    |                      |  |
|  |  |      |   | Filing Date: December 23, 2003 |    |                      |  |
| Date: January 7, 2005  |  | Page | 2 | of                             | 4  | Examiner: Unknown    |  |
|  |  |      |   |                                |    | Group Art Unit: 2851 |  |

| U.S. PATENT DOCUMENTS |    |                 |              |                                      |       |           |                              |
|-----------------------|----|-----------------|--------------|--------------------------------------|-------|-----------|------------------------------|
| Examiner's Initials*  |    | Document Number | Date MM/YYYY | Name (Family Name of First Inventor) | Class | Sub Class | Filing Date (if appropriate) |
| HN                    | AR | 6,560,032       | 05/2003      | HATANO                               | 359   | 656       |                              |
|                       | BR | 6,603,130       | 08/2003      | BISSCHOPS et al.                     | 250   | 492.1     |                              |
|                       | CR | 6,633,365       | 10/2003      | SUENAGA                              | 355   | 53        |                              |
|                       | DR | 2002/0163629    | 11/2002      | SWITKES et al.                       | 355   | 53        |                              |
|                       | ER | 2003/0123040    | 07/2003      | ALMOGY                               | 355   | 69        |                              |
|                       | FR | 2003/0174408    | 09/2003      | ROSTALSKI et al.                     | 359   | 642       |                              |
|                       | GR | 2004/0075895 A1 | 04/2004      | LIN                                  | 359   | 380       |                              |
| HN                    | HR | 2004/0109237 A1 | 06/2004      | EPPLÉ et al.                         |       |           |                              |
|                       | IR |                 |              |                                      |       |           |                              |

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|--------------------------|----|-----------------|--------------|---------|------------------|------------------|----|-------------------------------|----|
|                          |    | Document Number | Date MM/YYYY | Country | Inventor Name    | Enclosed         | No | Enclosed                      | No |
| HN                       | JR | JP 07-220990    | 08/1995      | JAPAN   | FUKUDA et al.    | X                |    |                               |    |
|                          | KR | JP 10-228661    | 08/1998      | JAPAN   | KUROKAWA         | X                |    |                               |    |
|                          | LR | JP 10-255319    | 09/1998      | JAPAN   | SUENAGA et al.   | X                |    |                               |    |
|                          | MR | JP 10-303114    | 11/1998      | JAPAN   | SUWA             | X                |    | X                             |    |
|                          | NR | JP 10-340846    | 12/1998      | JAPAN   | KUDO             | X                |    | X                             |    |
|                          | OR | JP 2001-091849  | 04/2001      | JAPAN   | AIZAKI et al.    | X                |    |                               |    |
|                          | PR | JP 07-132262    | 05/1995      | JAPAN   | HIRAKAWA et al.  | X                |    |                               |    |
|                          | QR | JP 58-202448    | 11/1983      | JAPAN   | KAWAMURA et al.  | X                |    |                               |    |
|                          | RR | WO 2004/019128  | 03/2004      | PCT     | OMURA et al.     | X                |    | X                             |    |
|                          | SR | WO 03/077037    | 09/2003      | PCT     | ROSTALSKI et al. | X                |    | X                             |    |
| HN                       | TR | WO 03/077036    | 09/2003      | PCT     | SCHUSTER         | X                |    |                               |    |
|                          | UR |                 |              |         |                  |                  |    |                               |    |

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| HN  | VR  | B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002                                   |  |
|   | WR  | B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997                |  |
|   | XR  | B.J. LIN, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269    |  |
|   | YR  | G.W.W. STEVENS, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72          |  |
|   | ZR  | S. OWA et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003 |  |
| HN  | AAR | S. OWA et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)   |  |

|          |           |                  |         |
|----------|-----------|------------------|---------|
| Examiner | H. Nguyen | Date Considered: | 6/13/05 |
|----------|-----------|------------------|---------|

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|  |  |      |   |                                |    |                      |  |
|--|--|------|---|--------------------------------|----|----------------------|--|
| FORM PTO-1449 (modified)<br>To: U.S. Department of Commerce<br>(PW FORM PAT-1449)<br>Patent and Trademark Office |  |      |   | Atty.<br>Dkt. No.              | M# | Client Ref.          |  |
|  |  |      |   | 307331                         |    | P-1774.000-US        |  |
| <b>INFORMATION DISCLOSURE STATEMENT<br/>BY APPLICANT</b>   |  |      |   | Applicant: VAN SANTEN et al.   |    |                      |  |
|  |  |      |   | Appln. No. 10/743,271          |    |                      |  |
|  |  |      |   | Filing Date: December 23, 2003 |    |                      |  |
| Date: January 7, 2005  |  | Page | 3 | of                             | 4  | Examiner: Unknown    |  |
|  |  |      |   |                                |    | Group Art Unit: 2851 |  |

| U.S. PATENT DOCUMENTS   |    |                    |                 |   |       |              |                                 |
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| Examiner's<br>Initials* |    | Document<br>Number | Date<br>MM/YYYY | Name<br>(Family Name of First Inventor) | Class | Sub<br>Class | Filing Date<br>(if appropriate) |
| HW                      | AR | 6,236,634 B1       | 05/2001         | LEE et al.                              | 369   | 112          |                                 |
| HW                      | BR | 2002/0020821 A1    | 02/2002         | VAN SANTEN et al.                       | 250   | 492          |                                 |

| FOREIGN PATENT DOCUMENTS |    |                    |                 |         |                  |  | English Abstract |    | Translation<br>Readily<br>Available |    |
|--------------------------|----|--------------------|-----------------|---------|------------------|--|------------------|----|-------------------------------------|----|
|                          |    | Document<br>Number | Date<br>MM/YYYY | Country | Inventor Name    |  | Enclosed         | No | Enclosed                            | No |
| HW                       | CR | DD 206 607         | 02/1984         | GERMANY | WESTPHAL et al.  |  |                  | X  |                                     |    |
|                          | DR | DD 221 563         | 04/1985         | GERMANY | PFORR et al.     |  |                  | X  |                                     |    |
|                          | ER | JP 11-176727       | 07/1999         | JAPAN   | SHIRAI           |  | X                |    |                                     |    |
|                          | FR | JP 2000-058436     | 02/2000         | JAPAN   | FUJISHIMA et al. |  | X                |    |                                     |    |
|                          | GR | WO 2004/053950 A1  | 06/2004         | PCT     | OWA              |  | X                |    |                                     |    |
|                          | HR | WO 2004/053951 A1  | 06/2004         | PCT     | MAGOME et al.    |  | X                |    |                                     |    |
|                          | IR | WO 2004/053952 A1  | 06/2004         | PCT     | MAGOME et al.    |  | X                |    |                                     |    |
|                          | JR | WO 2004/053953 A1  | 06/2004         | PCT     | NEI et al.       |  | X                |    |                                     |    |
|                          | KR | WO 2004/053954 A1  | 06/2004         | PCT     | NEI et al.       |  | X                |    |                                     |    |
|                          | LR | WO 2004/053955 A1  | 06/2004         | PCT     | HIRUKAWA et al.  |  | X                |    |                                     |    |
|                          | MR | WO 2004/053956 A1  | 06/2004         | PCT     | NAGASAKA et al.  |  | X                |    |                                     |    |
|                          | NR | WO 2004/053957 A1  | 06/2004         | PCT     | HIDAKA et al.    |  | X                |    |                                     |    |
|                          | OR | WO 2004/053958 A1  | 06/2004         | PCT     | MIZUTANI et al.  |  | X                |    |                                     |    |
|                          | PR | WO 2004/053959 A1  | 06/2004         | PCT     | SHIRAI           |  | X                |    |                                     |    |
| HW                       | QR | WO 2004/053596 A2  | 06/2004         | PCT     | GRAUPNER         |  | X                |    |                                     |    |

| OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.) |    |   |  |  |  |  |  |  |  |  |
|---|----|---|--|--|--|--|--|--|--|--|
| HW  | RR | Nikon Precision Europe GmbH, "Investor Relations – Nikon's Real Solutions", May 15, 2003  |  |  |  |  |  |  |  |  |
|   | SR | H. KAWATA et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36              |  |  |  |  |  |  |  |  |
|   | TR | J.A. HOFFNAGLE et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309   |  |  |  |  |  |  |  |  |
|   | UR | B.W. SMITH et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003   |  |  |  |  |  |  |  |  |
|   | VR | H. KAWATA et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177 |  |  |  |  |  |  |  |  |
| HW  | WR | G. OWEN et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036  |  |  |  |  |  |  |  |  |
|   | XR |   |  |  |  |  |  |  |  |  |
|   | YR |   |  |  |  |  |  |  |  |  |

|          |           |                  |         |
|----------|-----------|------------------|---------|
| Examiner | H. Nguyen | Date Considered: | 6/13/05 |
|----------|-----------|------------------|---------|

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FORM PTO-1449 (modified)  
To: U.S. Department of Commerce  
(PW FORM PAT-1449)  
Patent and Trademark Office

Atty.  
Dkt. No.

M#

Client Ref.

307331

P-1774.000-US

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: VAN SANTEN et al.

Appl. No. 10/743,271

Filing Date: December 23, 2003

Date: January 7, 2005

Page 4 of 4

Examiner: Unknown

Group Art Unit: 2851

**U.S. PATENT DOCUMENTS**

| Examiner's<br>Initials* | Document<br>Number | Date<br>MM/YYYY | Name<br>(Family Name of First Inventor) | Class | Sub<br>Class | Filing Date<br>(if appropriate) |
|-------------------------|--------------------|-----------------|---|-------|--------------|---------------------------------|
| HW                      | ZR 2004/0119954    | 06/2004         | KAWASHIMA et al.                        | 355   | 30           |                                 |
| HW                      | AAR 2004/0125351   | 07/2004         | KRAUTSCHIK et al.                       | 355   | 53           |                                 |
|                         | BBR                |                 |   |       |              |                                 |
|                         | CCR                |                 |   |       |              |                                 |
|                         | DDR                |                 |   |       |              |                                 |
|                         | EER                |                 |   |       |              |                                 |
|                         | FFR                |                 |   |       |              |                                 |
|                         | GGR                |                 |   |       |              |                                 |

**FOREIGN PATENT DOCUMENTS**

|    | Document<br>Number    | Date<br>MM/YYYY | Country | Inventor Name     | English Abstract |    | Translation<br>Readily<br>Available |    |
|----|-----------------------|-----------------|---------|-------------------|------------------|----|-------------------------------------|----|
|    |                       |                 |         |                   | Enclosed         | No | Enclosed                            | No |
| HW | HHR WO 2004/055803 A1 | 07/2004         | PCT     | VAN SANTEN        | X                |    | X                                   |    |
| I  | IIR WO 2004/057589 A1 | 07/2004         | PCT     | NEIJZEN et al.    | X                |    | X                                   |    |
| J  | JJR WO 2004/057590 A1 | 07/2004         | PCT     | VAN SANTEN et al. | X                |    | X                                   |    |
| HW | KKR JP 2004-193252    | 07/2004         | JAPAN   | Not Available     | X                |    |                                     |    |
|    | LLR                   |                 |         |                   |                  |    |                                     |    |
|    | MMR                   |                 |         |                   |                  |    |                                     |    |
|    | NNR                   |                 |         |                   |                  |    |                                     |    |
|    | OOR                   |                 |         |                   |                  |    |                                     |    |

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

|    |     |  |  |  |  |
|----|-----|--|--|--|--|
| HW | PPR | S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51                                     |  |  |  |
| I  | QQR | H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22                                       |  |  |  |
| J  | RRR | T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004  |  |  |  |
|    | SSR | "Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521                         |  |  |  |
|    | TTR | A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004  |  |  |  |
| HW | UUR | B. LIN, "The $k_3$ coefficient in nonparaxial MNA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002) |  |  |  |
|    | VVR |  |  |  |  |
|    | WWR |  |  |  |  |
|    | XXR |  |  |  |  |
|    | YYR |  |  |  |  |
|    | ZZR |  |  |  |  |

Examiner

H. Nguyen

Date Considered:

6/13/05

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

Docket Number: 081468-0307331  
Client Reference: P-1774.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE.

In Re the Application of  
ELMAR VAN SANTEN et al.  
Application No.: 10/743,271

Group Art Unit:

Examiner: Unassigned

Filed: December 23, 2003

Confirmation No.: Unassigned

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

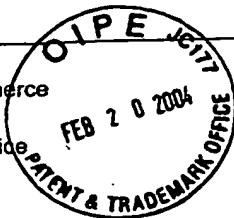
Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

| Examiner's Initials | First Inventor                 | Application No. | Filing Date | Enclosed   |
|---------------------|--------------------------------|-----------------|-------------|--|
|                     | Joeri LOF et al.               | 10/705,805      | 11/12/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | Joeri LOF et al.               | 10/705,783      | 11/12/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | Johannes C.H. MULKENS et al.   | 10/743,266      | 12/23/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | Klaus SIMON et al.             | 10/724,402      | 12/01/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | Joannes T. DESMIT et al.       | 10/705,804      | 11/12/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
|                     | Antonius T.A.M. DERKSEN et al. | 10/705,785      | 11/12/2003  | <input checked="" type="checkbox"/> Specification<br><input checked="" type="checkbox"/> Drawings<br><input checked="" type="checkbox"/> Other: stamped receipt card |
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\*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.



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**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: Helmar VAN SANTEN et al.

Appln. No.: 10/743,271

Filing Date: December 23, 2003

Date: February 20, 2004

Page

1

of

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Examiner: Unassigned

Group Art Unit: Unassigned

**U.S. PATENT DOCUMENTS**

| Examiner's<br>Initials* | Document<br>Number | Date<br>MM/YYYY | Name<br>(Family Name of First Inventor) | Class | Sub<br>Class | Filing<br>Date<br>(if appropriate) |
|-------------------------|--------------------|-----------------|---|-------|--------------|------------------------------------|
| HW                      | AR 2004/0000627A1  | 01/01/2004      | Karl-Heinz SCHUSTER                     |       |              |                                    |
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| HW                      | CR 2004/0021844 A1 | 02/05/2004      | Yutaka SUENAGA                          |       |              |                                    |
|                         | DR                 |                 |   |       |              |                                    |
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|                         | FR                 |                 |   |       |              |                                    |
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|                         | HR                 |                 |   |       |              |                                    |
|                         | IR                 |                 |   |       |              |                                    |
|                         | JR                 |                 |   |       |              |                                    |
|                         | KR                 |                 |   |       |              |                                    |
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|                         | MR                 |                 |   |       |              |                                    |
|                         | NR                 |                 |   |       |              |                                    |

**FOREIGN PATENT DOCUMENTS**

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|--|--------------------|-----------------|---------|---------------|---------------------|----|-------------------------------------|----|
|  |                    |                 |         |               | Enclosed            | No | Enclose                             | No |
|  | OR                 |                 |         |               |                     |    |                                     |    |
|  | PR                 |                 |         |               |                     |    |                                     |    |
|  | QR                 |                 |         |               |                     |    |                                     |    |
|  | RR                 |                 |         |               |                     |    |                                     |    |
|  | SR                 |                 |         |               |                     |    |                                     |    |
|  | TR                 |                 |         |               |                     |    |                                     |    |
|  | UR                 |                 |         |               |                     |    |                                     |    |
|  | VR                 |                 |         |               |                     |    |                                     |    |
|  | WR                 |                 |         |               |                     |    |                                     |    |
|  | XR                 |                 |         |               |                     |    |                                     |    |

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|    | DDR |  |  |  |  |

Examiner

H. Nguyen

Date Considered:

6/13/2005

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.